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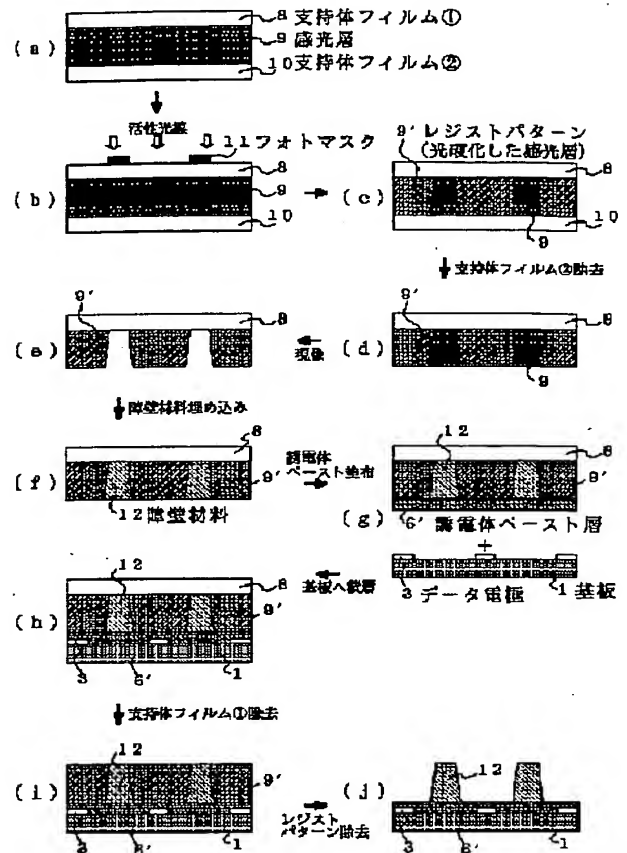
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TITLE : PRODUCTION OF SUBSTRATE FOR
PLASMA DISPLAY PANEL



ABSTRACT : PROBLEM TO BE SOLVED: To provide a process for producing a substrate for a plasma display panel which may be produced with a smaller number of stages and a process for producing the substrate for the plasma display panel which maintains high- accuracy shapes by simultaneously executing the formation of PDP dielectric layers and barrier formation.

SOLUTION: This process for producing the substrate for the plasma display panel consists in transferring the barrier materials embedded into the recessed parts of a base body onto a substrate 1 and forming the patterns corresponding to the recessed parts of the base body onto the substrate 1, then baking the patterned barrier materials. The dielectric paste layers 6' and the barrier materials are transferred onto the substrate 1 from the base body which has the recessed parts and has the dielectric paste layers formed on the barrier materials embedded into the recessed parts and the surface exclusive of the recessed parts, by which the patterns consisting of the barrier materials corresponding to the recessed parts are formed. These dielectric paste layers 6' and patterned barrier materials are then baked.

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